



High brightness EUV source for EUVL applications

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Outline

- Laboratory for Energy Conversion, ETH.
- Applied Laser Plasma Science (ALPS) Facility.
- Droplet Dispenser.
- Computational Studies of Droplets.
- Droplet Stability Measurements.
- Droplet-by-Droplet Triggering.
- Pinhole camera and spotsize measurements.
- High Brightness Collector and I.F. measurements.
- EUV radiation measurements and results.
- Adlyte Ltd. Products: Debris mitigation results from HPS.

Laboratory for Energy Conversion

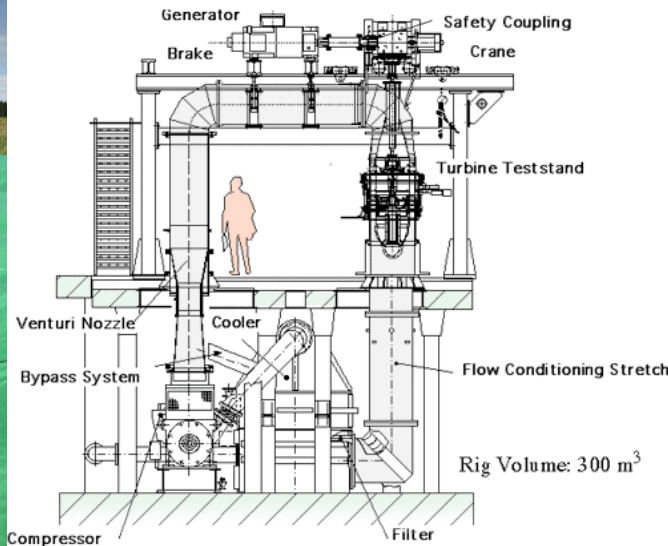


Figure 1:2 Sensor FRAP Probe with 1.8mm tip outer diameter of LEC.

People:

•64 members of staff including PhD students, post-docs, Msc students, Electrical engineers and Workshop technicians.

Fields of Research:

- Power, Energy and Turbomachinery
- Applied Laser Plasma Science
- Environmental and Renewable Energy
- Instrumentation

Applied Laser Plasma Science (ALPS) Facility

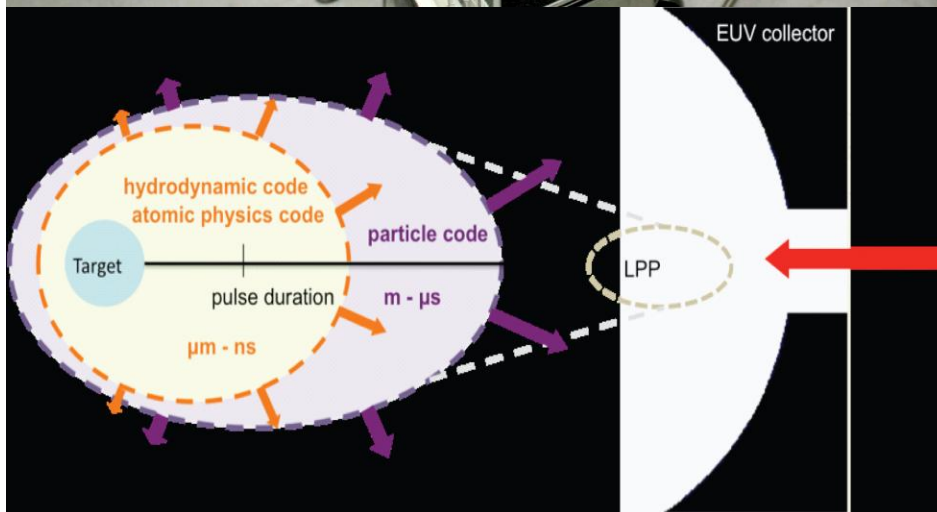


Laboratory:

- AO16 Nd:YAG Laser, 1064 nm, 20 kHz, 1.6 kW.
- Entire system automated from a single control unit.

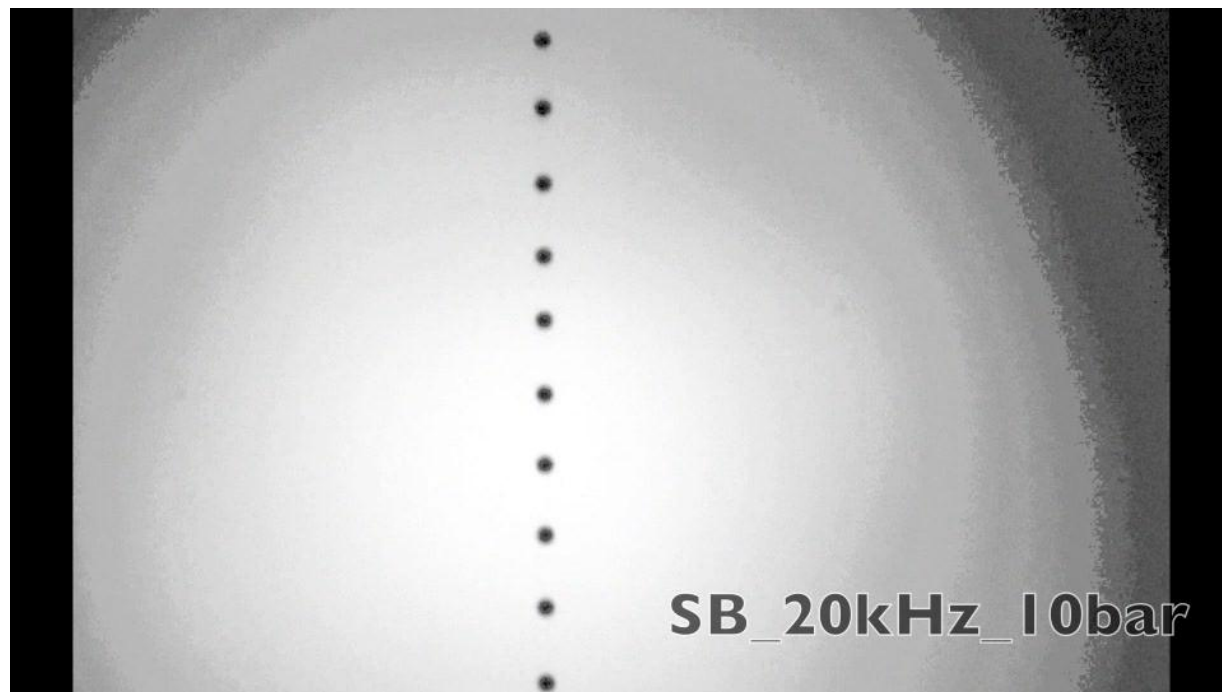
Computational studies:

- 2-D/axisymmetric hydrodynamic-particle code used to model plasma expansion from laser-droplet interaction up to the collector optic.





Droplet Dispenser



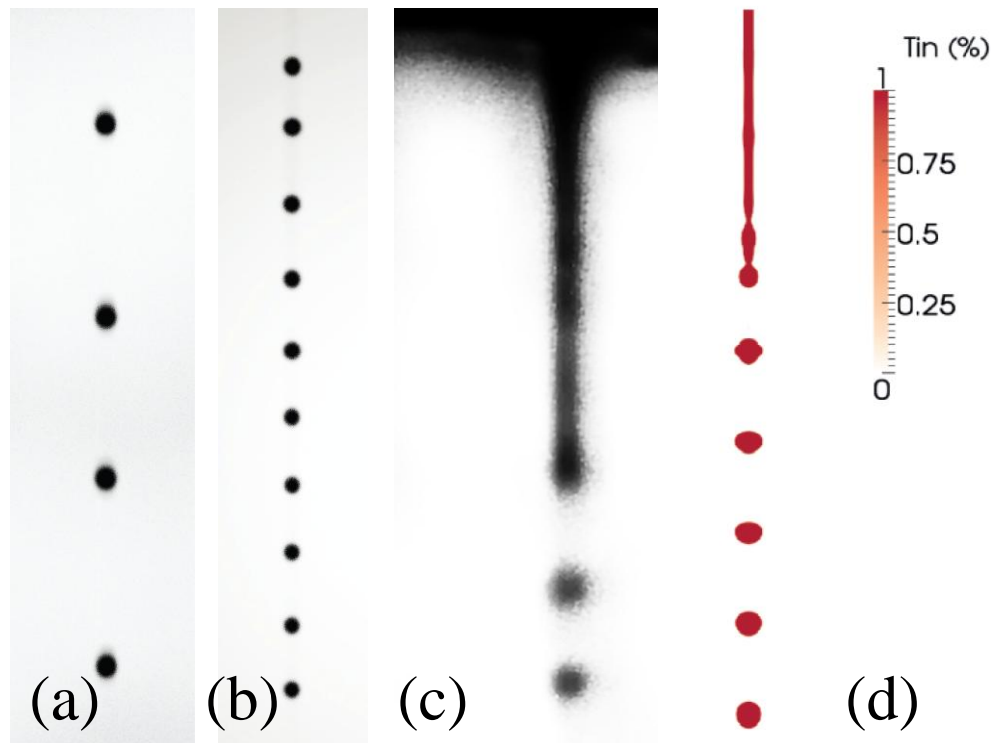
- Images recorded using Xe flash and macroscope.
- Single droplet exposure.
- Measurements recorded at 5 Hz.

Computational Studies of Droplets

Droplet generator development is supported by experimentally validated computational simulations of droplet formation.

100 kHz droplet validation

	Experiment	Simulation	Dev
Diameter	38um	43um	13%
Velocity	12.1m/s	11.1m/s	9%



(a) Droplet train at 18 kHz, diameter 58 μm .

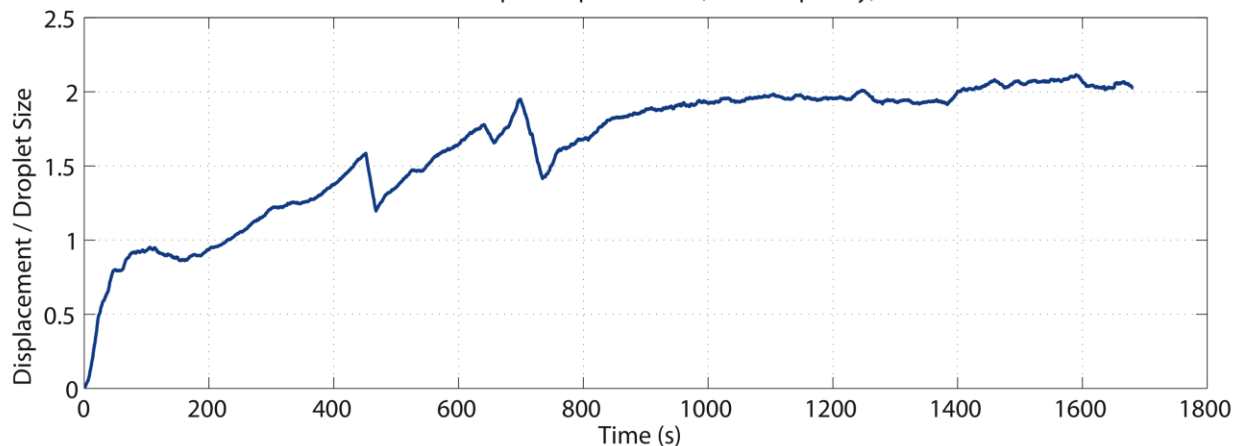
(b) Droplet train images at 50 kHz, diameter 43 μm .

(c) Rayleigh break-up observed at nozzle exit.

(d) Computational simulations of the Rayleigh break-up at nozzle exit.

Droplet Stability: Results from droplet imaging

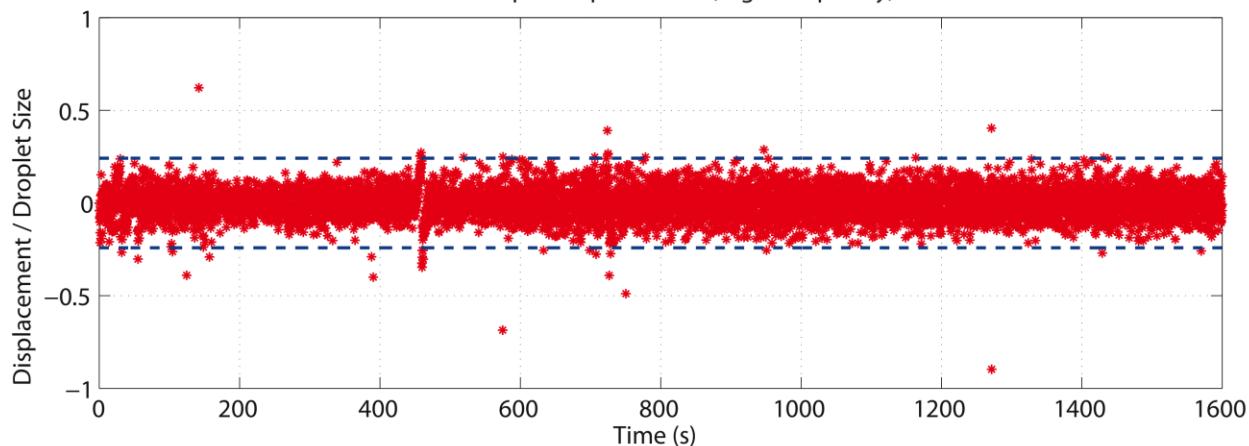
Lateral droplet displacement (Low Frequency)



Results derived from droplet imaging.

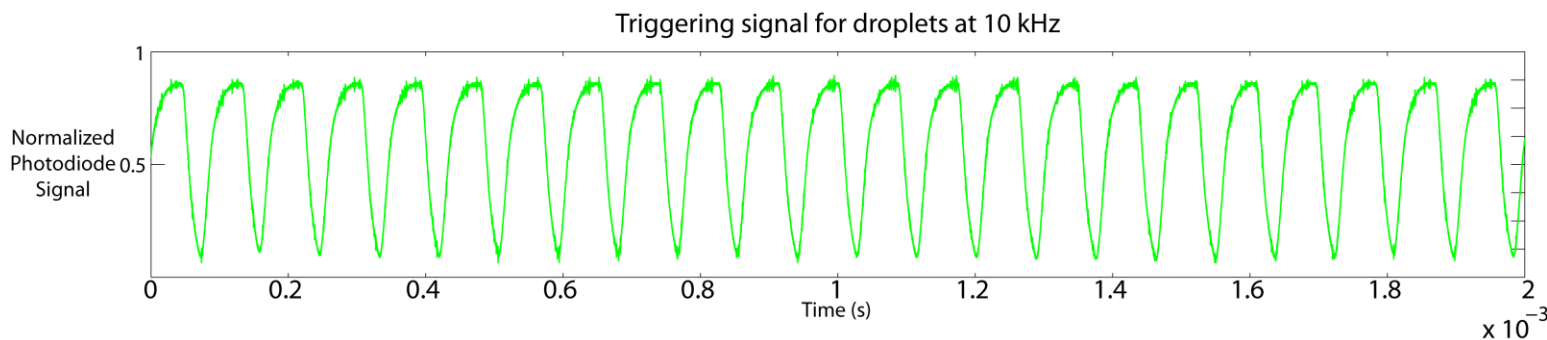
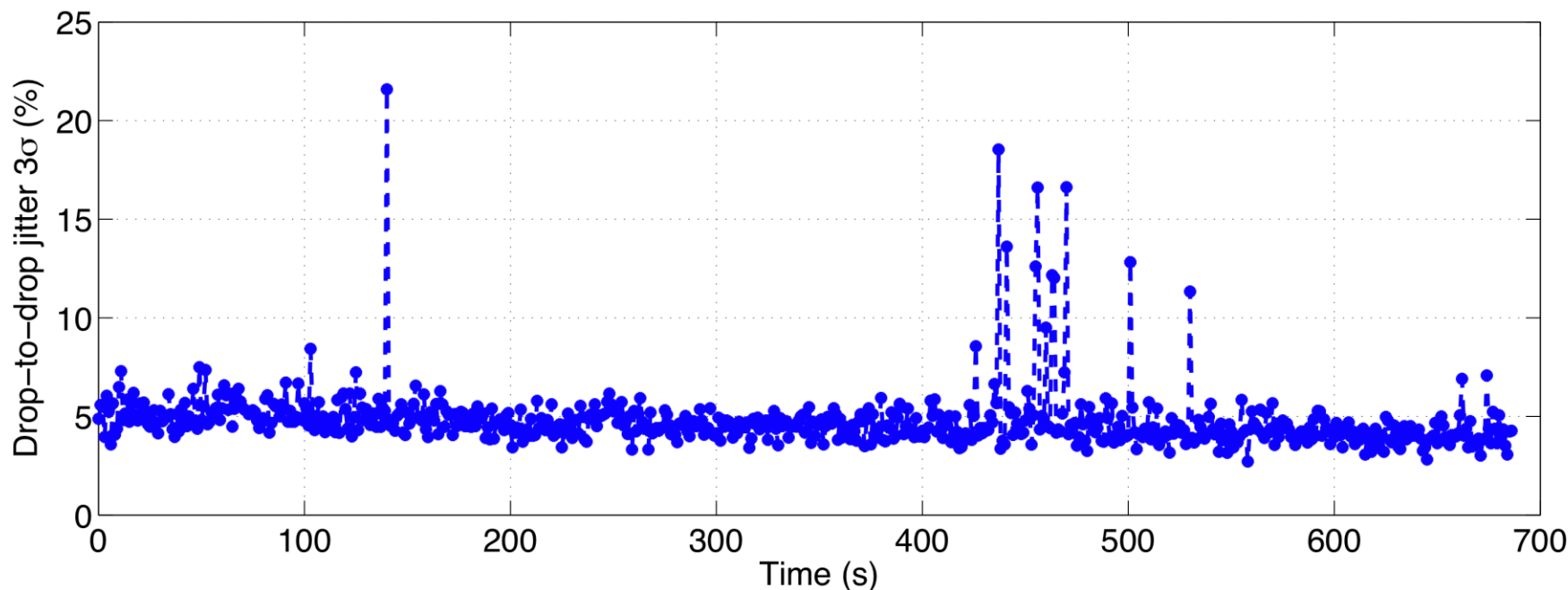
(A) Low frequency content (Hz scale) of lateral displacement.

Lateral droplet displacement (High Frequency)

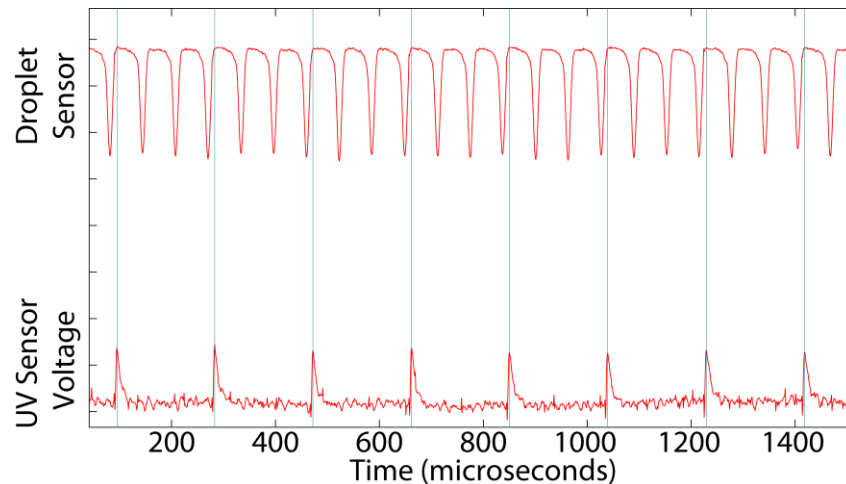
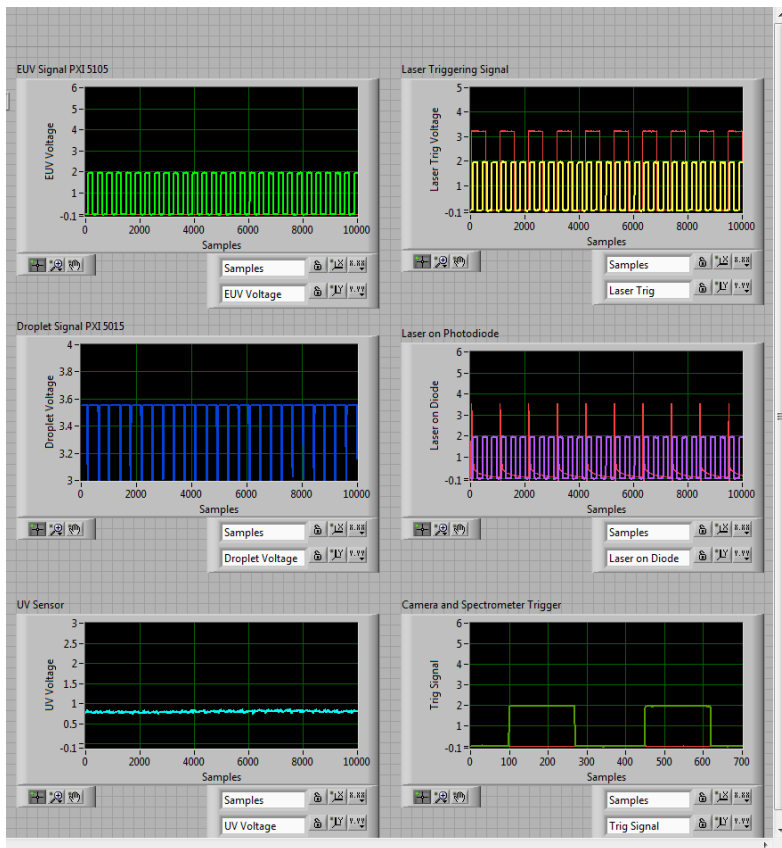


(B) High frequency content (kHz scale) of lateral displacement.

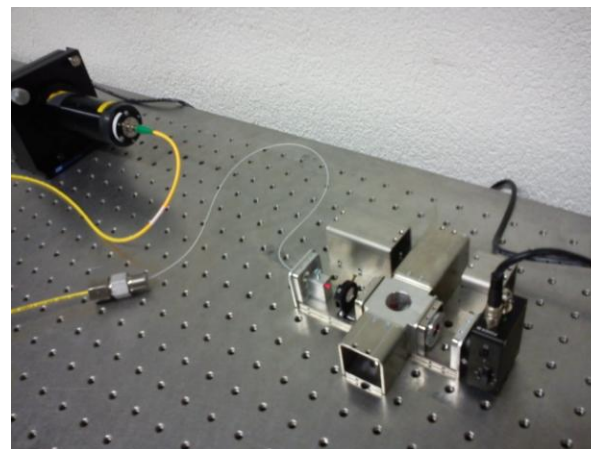
Droplet Stability: Laser/Photodiode measurements



Droplet by droplet triggering



- Laser triggered to hit every third droplet.
- 100% hit-rate.

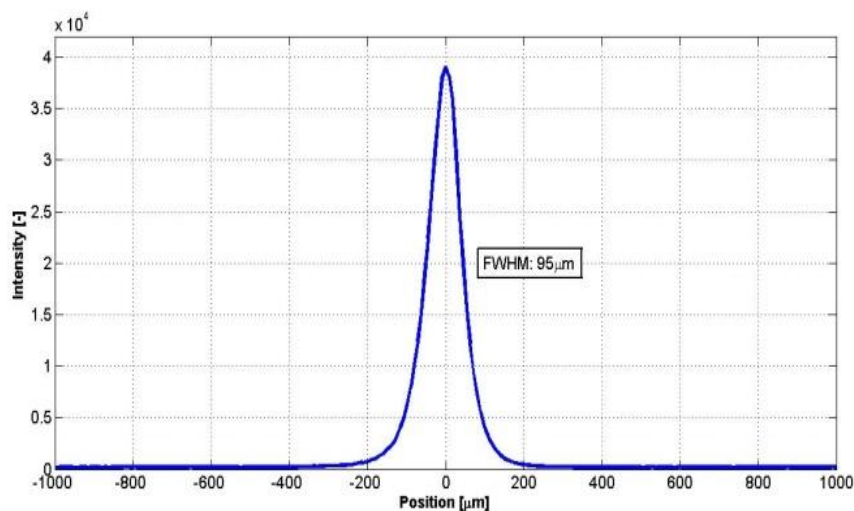
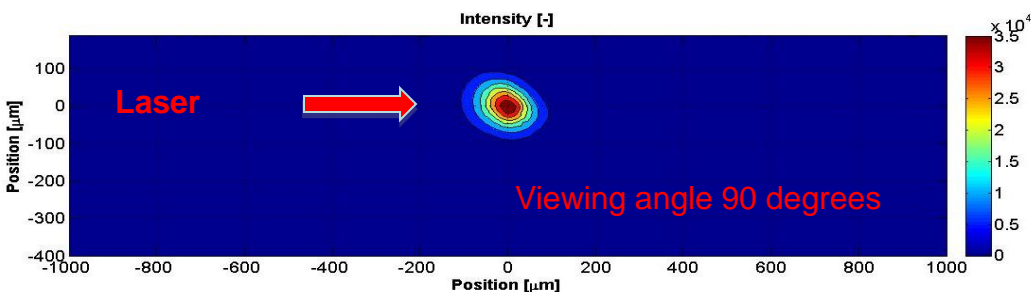


adlyte

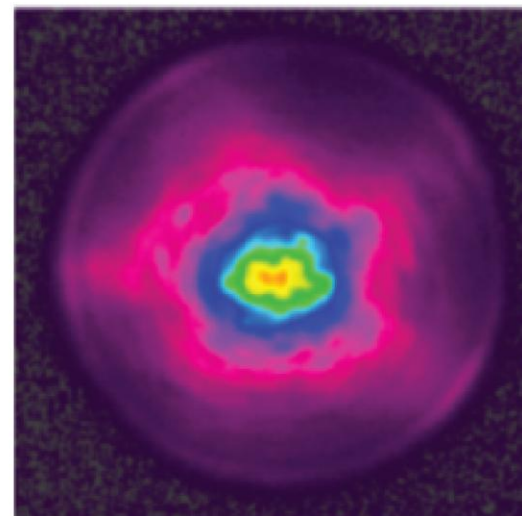
- All signals simultaneously recorded by the control system.
- Droplet Signals are used to directly trigger the laser to compensate for temporal Jitter.

Pinhole Camera and Spotsize Measurements

EUV source size: 95 micron FWHM

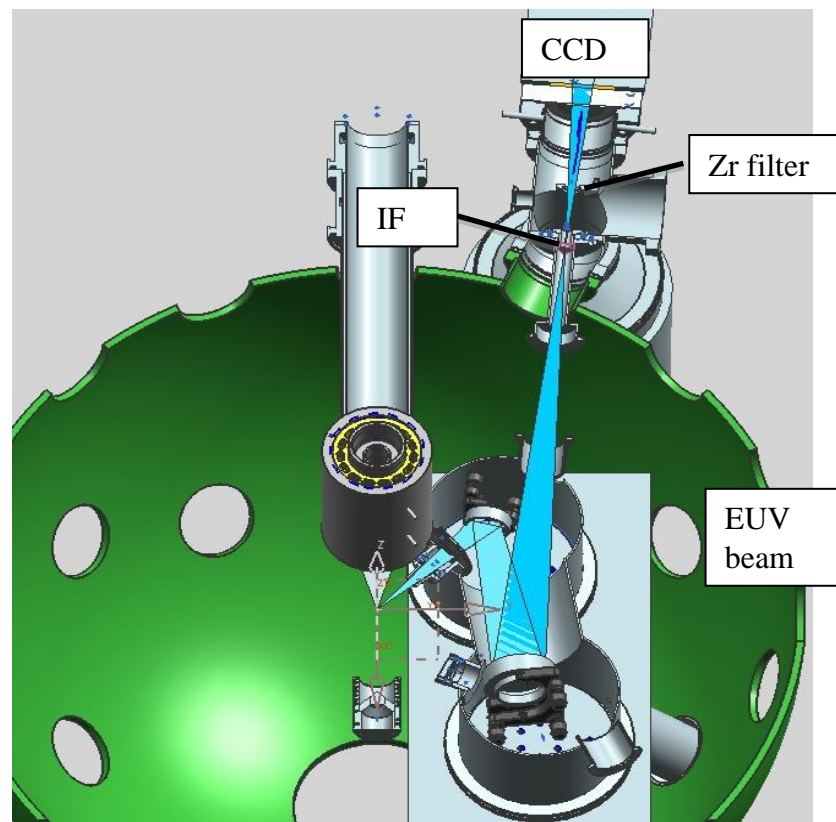
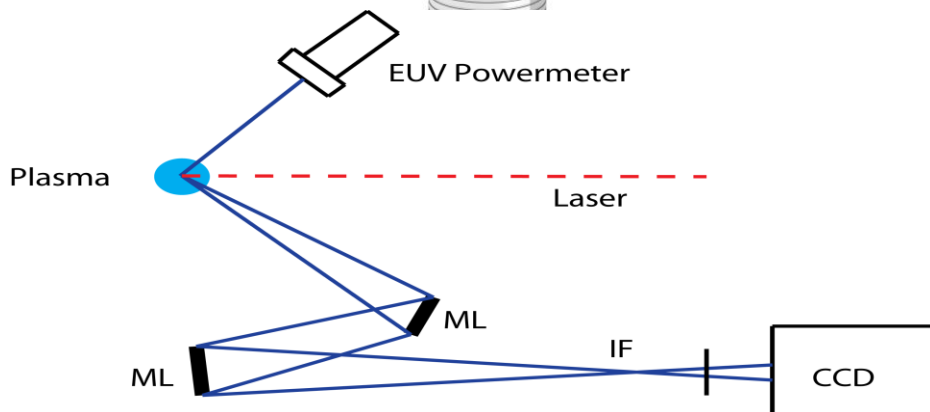
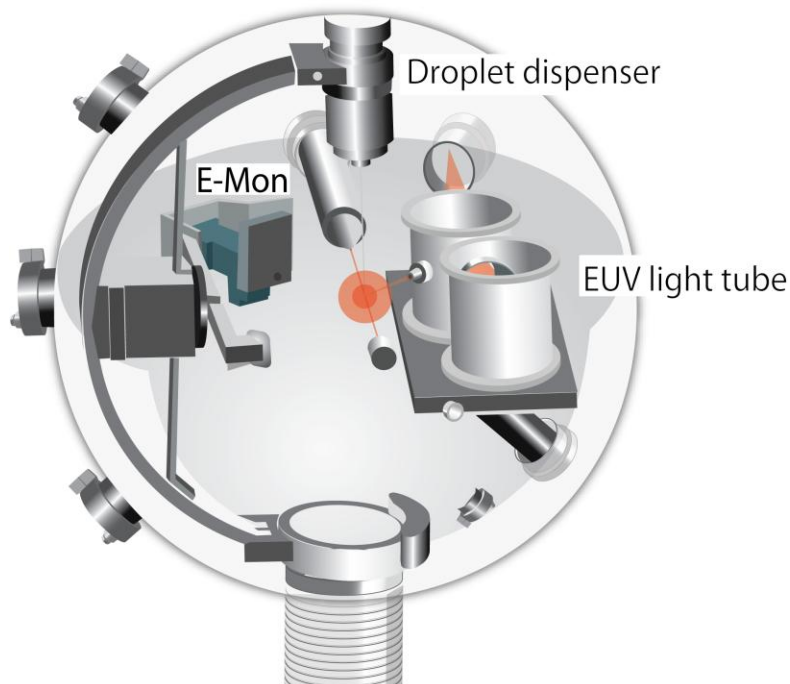


Laser spot at focus



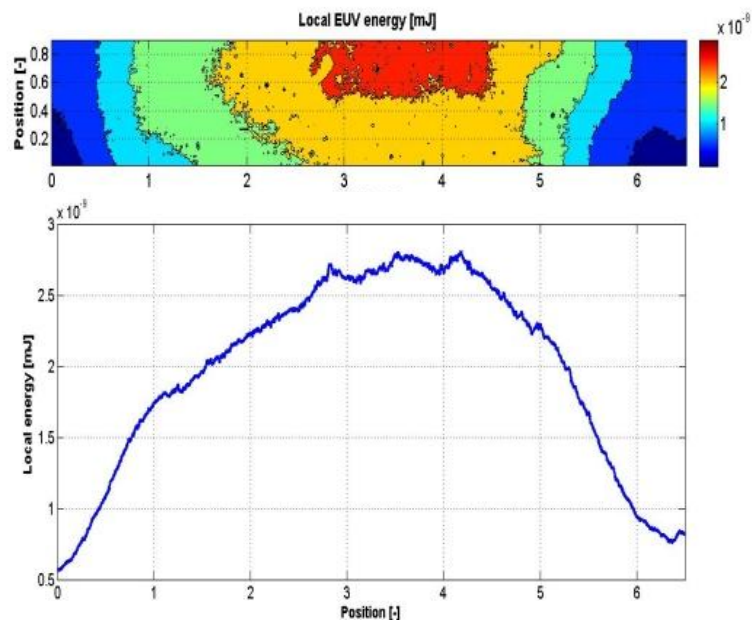
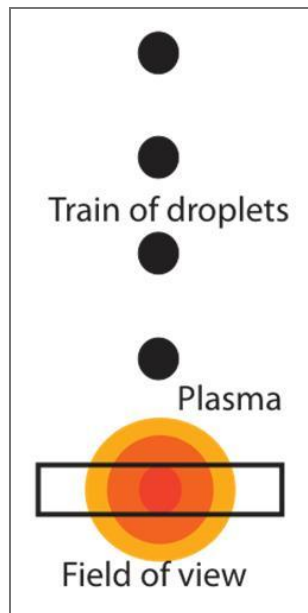
Focused laser spotsize:
78 micron.
Spiricon Image of the AO16
laser pulse.

High Brightness Collector



CCD Camera is used to measure the radiation pattern after the IF.

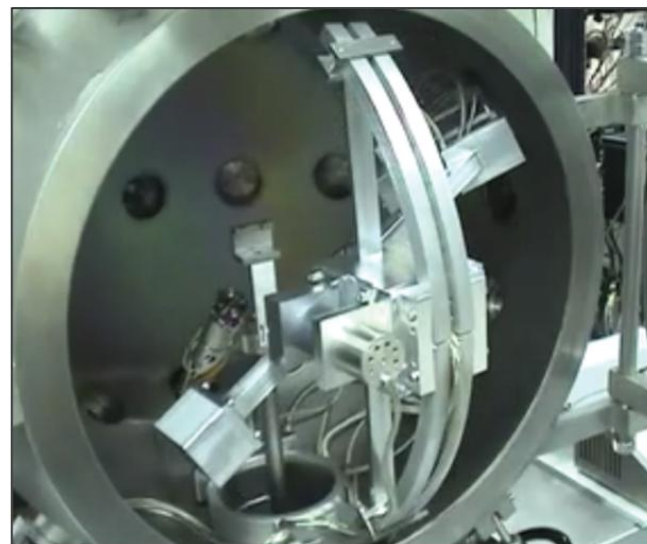
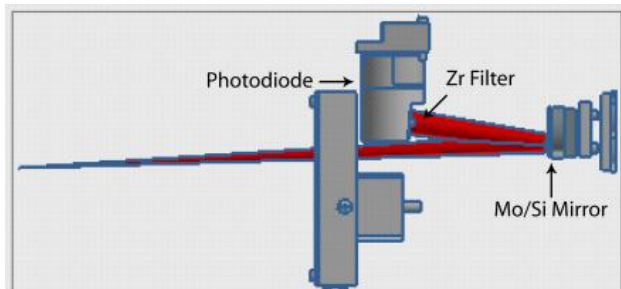
Collector Optics Module



- CCD positioned at a distance from IF to maximize spatial resolution of recorded EUV signals.
- Reflectivity of mirrors, transmission of filter and Quantum Efficiency of CCD are used to determine EUV power at IF.
- EUV Power measurements at the IF are cross calibrated with Energy Monitor measurements.

EUV Radiation Measurements

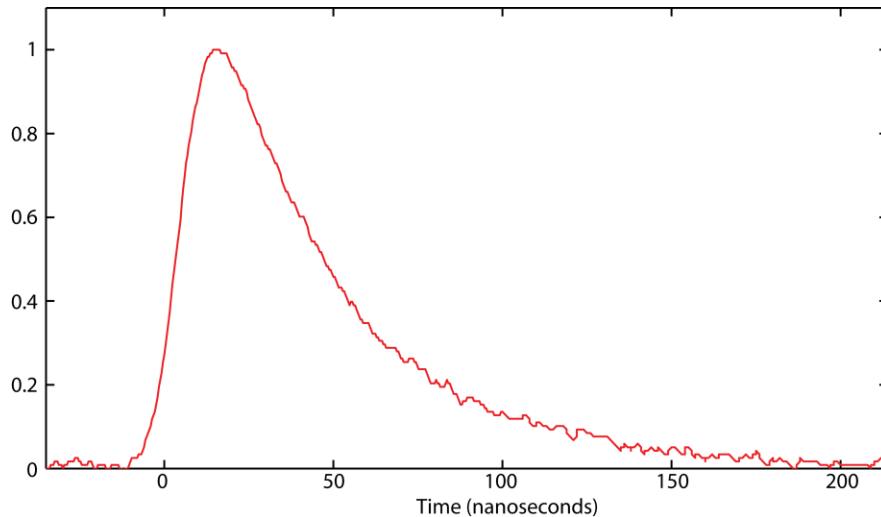
- EUV source power measured with a calibrated energy monitor.
- Measurements recorded at 45 deg w.r.t. laser axis to complement acceptance angle of LPS entrance aperture.



Energy Monitor mounted on robotic arm for 2π sr measurements.



EUV Radiation Measurements



EUV Source Measurement:
Conversion Efficiency: 1.05%

Parameters	Measured
Laser power on target (W)	1100
Laser Frequency (kHz)	6
Laser focal spot size (μm)	78
EUV source size (μm)	95 at FWHM
Average Conversion efficiency (%)	1.05%
Source brightness ($\text{W}/\text{mm}^2/\text{sr}$)	≈ 259

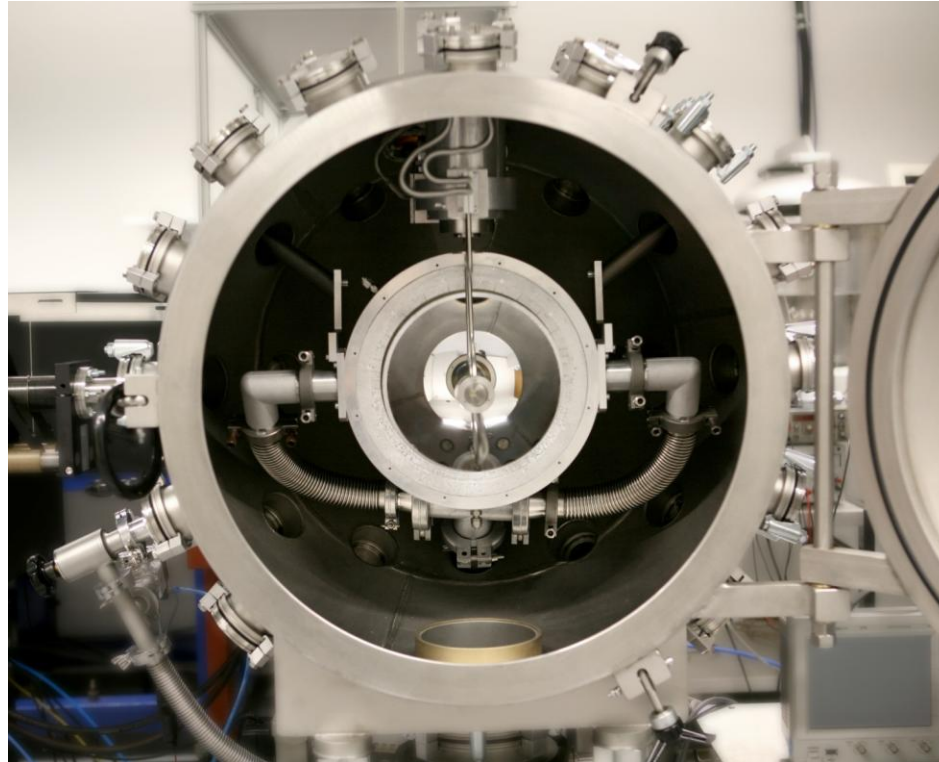


Ongoing Work

- Present Science and Technology Development continuing.
- To commercialize, an ETH spin-off company called Adlyte Ltd was formed in 2009.
- Currently Adlyte is working with customers in the metrology and inspection fields.

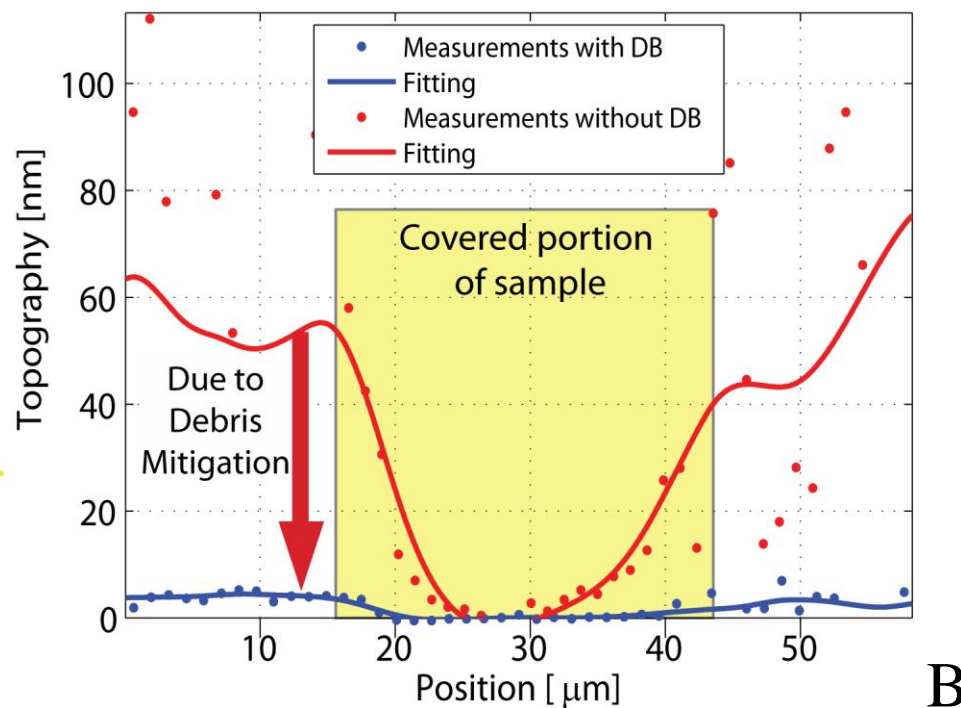
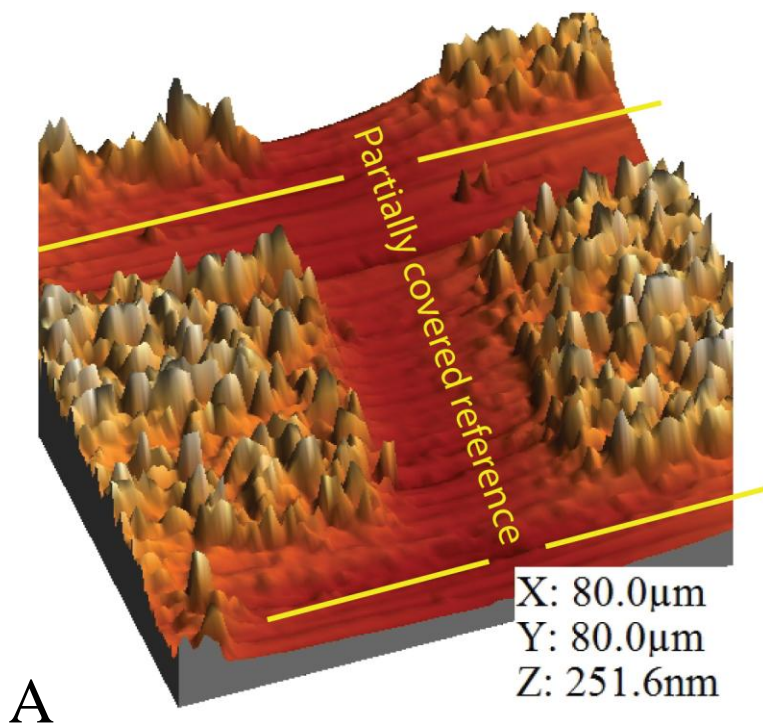


High power EUV source (HPS)



- Integrated debris mitigation system.
- Integrated collector cooling.
- Large solid angle, 4 sr.
- High IF power.

Debris Mitigation

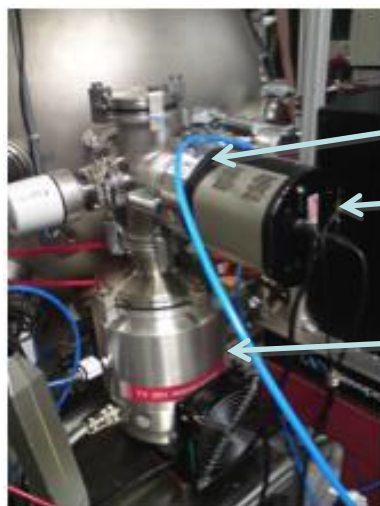
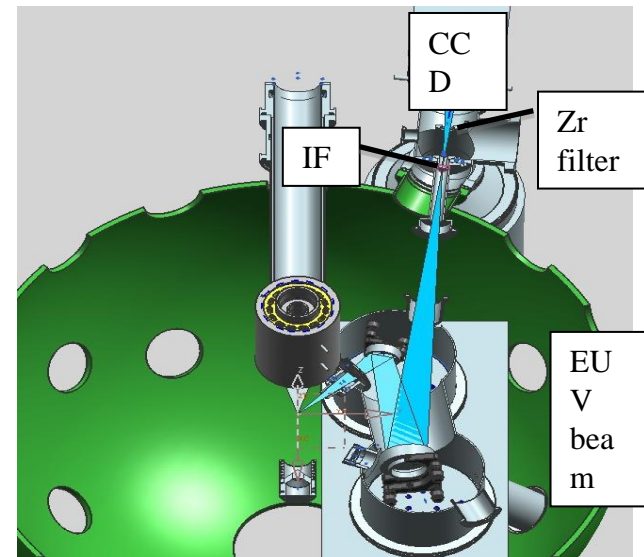


A: AFM measurement sample without debris mitigation.

B: Comparison of samples with and without debris mitigation.



Low power EUV source (LPS)

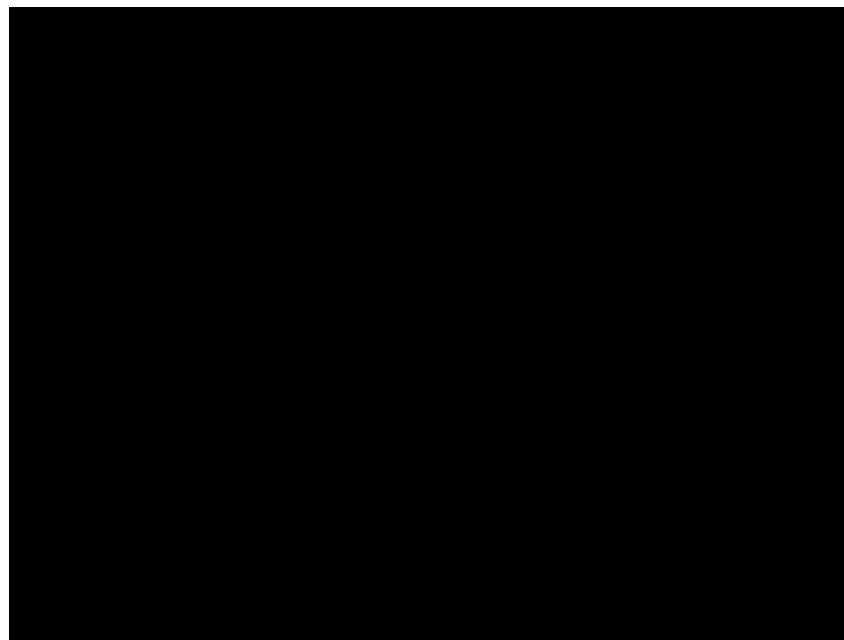


Low power EUV source:
O.1 Sr Collector



Questions

- **Thank you for your time.**



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